

PATENT APPLICATION
Do. No. 1941-76

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Jun LIU; Karel DOMANSKY; Xiohong LI; Glen E.
FRYXELL; Suresh BASKARAN; Nathan J. KOHLER; and Suntharampillai
THEVUTHASAN

Serial No. 09/837,885

Examiner: Lcanna Roche

Filed: April 18, 2001

Group Art Unit: 1771

For: MESOPOROUS SILICA FILM FROM A SOLUTION CONTAINING
A SURFACTANT AND METHODS OF MAKING SAME

Date: April 2, 2002

BOX FEE AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

SECOND PRELIMINARY AMENDMENT

Please amend the application as follows, prior to examination of the
application on its merits.

IN THE CLAIMS

Please revise the claims as follows:

1. A mesoporous silica film prepared from a surfactant containing
solution, having a dielectric constant less than 3 that has both a relative stability and
an absolute stability in a humid atmosphere, a film thickness from about 0.1 μm to
about 1.5 μm , and an average pore diameter less than or equal to about 20 nm.

2. The mesoporous silica film as recited in claim 1, wherein said average
pore diameter is less than or equal to about 10 nm.

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lower limit
is ~1 nm,
inherent to
"mesoporous"